

In place of PTO-1449 Form		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		Complete if Known	
MAY 13 2004 INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number		10/715,326	
		Filing Date		November 17, 2003	
		Applicant(s)		Yu-Liang Hsu, et al.	
		Art Unit		2812 2813	
		Examiner Name		To Be Determined Nguyen	
SHEET 1 OF 1		Attorney Docket Number		24061.51 (TSMC2002-1216)	

U. S. PATENT DOCUMENTS				
Examiner's Initials	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
IN	AA	5,725,987	03-10-1998	Combes, et al.
	AB	6,306,754	10-23-2001	Agarwal
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Examiner's Initials	Cite No.	Foreign Patent Document (Country Code - Number - Kind)	Publication Date MM-DD-YYYY	Patentee or Applicant of Cited Document	Translation Y/N

OTHER PRIOR ART		
Examiner's Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article, title of the item, date, page(s), volume-issue number(s), publisher, city/country where published
TA	AL	ALMANZA-WORKMAN, A. MARCIA, et al., "Water Dispersible Silanes for Wettability Modification of Polysilicon", Journal of the Electrochemical Society, 149, 2002, pp. H6-H11.
TA	AM	WEIBEL, GINA L., et al., "An Overview of Supercritical CO ₂ Applications in Microelectronics Processing", Microelectronic Engineering 65, 2003, pp. 145-152.

Examiner Signature	<i>[Signature]</i>	Date Considered	7/13/05
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include a copy of this form with next communication to applicant.